

ABSTRACT

In the manufacture of a photomask blank, a seed layer
5 of a chromium material containing oxygen, nitrogen and/or
carbon is formed on a transparent substrate before a light-
shielding film and an antireflective film are deposited
thereon. Any film on the seed layer builds up in accordance
10 with fine granular growth, and so the resulting photomask
blank has an improved surface roughness, which enables high-
sensitivity detection in the process of defect inspection
and circuit pattern inspection. By lithographically
patterning the photomask blank, a photomask is fabricated.

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